[Document Name] Abstract

[Abstract]

[Problem to be Solved]

To prevent fine-particle dust from being swirled up by movement of a moving stage that is used in an atmosphere-adjusted processing room and adopts gas floating.

[Solution]

Provided is a moving stage 3 that is installed in a processing room 2 in which a processing target (semiconductor substrate 100) is processed under an adjusted atmosphere, including: a stage main body 30 on which the processing target is placed; and a gas support unit that supports the stage main body 30 in a non-contact manner by a gas pressure. The gas support unit includes one or more gas pads 35 that face at least a lying surface or/and a standing surface of the processing room 2 and each blow out gas toward the surface. A fine-particle dust suction port 42 is provided around each of the gas pads 35. A suctioned gas exhaust line (suctioned gas exhaust pipe 43) extended to an outside of the processing room is provided so as to be communicated with the fine-particle dust suction port 42.

[Selected Drawing] Figure 2